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Santa Clara, CA – EE Times published today an interview with David K. Lam, Chairman of Multibeam Corporation.

The article introduces Multibeam's Complementary Electron-Beam Lithography (CEBL), which enables cost-effective production of microchips at upcoming technology generations.

Lam explained that "CEBL 'complements' or works in tandem with today's 193-nm immersion tools...We are not an NGL. We will not replace optical in high-volume manufacturing anytime soon."

EE Times editor Mark LaPedus observed that "Multibeam is somewhat taking a page from Intel Corp., which has been pushing a "complementary" lithography strategy. The chip giant hopes to push 193-nm immersion to 11-nm. Then, at 11-nm, Intel is pushing its concept of a "complementary" or mix-and-match strategy..."

The industry has taken note of Multibeam's CEBL. Multibeam is in discussions with leading equipment suppliers and chip makers in using CEBL in next-generation chip production. CEBL, designed to work hand-in-hand with existing Optical Lithography to reduce risk and cost, is compatible with industry's lithography infrastructure.

The EE Times article can be found online at:

<http://www.eetimes.com/electronics-news/4213579/Startup-rolls-complementary-litho>

#### **About David Lam**

David K. Lam is probably best known for Lam Research (NSDQ: LRCX), which he founded in 1980. Under his guidance as CEO, the company introduced the industry's first fully automated plasma etching system for semiconductor manufacturing. Lam Research, headquartered in Fremont, California, has since become a global leader in semiconductor capital equipment. Lam uses his experience and expertise to provide guidance to emerging technology enterprises, including Microprobe, Xradia, and Multibeam. Lam received his Ph.D. in engineering from M.I.T.

#### **About Multibeam Corporation**

Multibeam is the technology leader in high-speed multiple-column E-Beam Lithography (EBL). In 2011, Multibeam introduced Complementary EBL (CEBL). CEBL extends Optical Lithography and enables the production of next-generation semiconductors in high volumes at reduced cost. Multibeam is led by Dr. David K. Lam. More information is available at [www.multibeamcorp.com](http://www.multibeamcorp.com).

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